

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A plasma source apparatus, comprising :
 - a. a resonant antenna,
 - b. a plasma generation chamber in the proximity of the antenna,
 - c. a fluid injector for introducing at least one fluid into the plasma generation chamber,
 - d. a radio frequency generator with continuous or pulsed RF power supply,
~~characterized by the fact that~~wherein said antenna comprises two conductive loop elements spaced along a common longitudinal axis and at least one axial conductive segment electrically interconnecting said conductive loop elements, each of said conductive loop elements and/or said axial conductive segment including at least one capacitive element.
2. (original) Plasma source apparatus according to claim 1 wherein only said conductive loop elements include at least one capacitive element.
3. (original) Plasma source apparatus according to claim 1 wherein only said axial conductive element includes at least one capacitive element.
4. (original) Plasma source apparatus according to claim 1 wherein said conductive loop elements and said axial conductive segment include at least one capacitive element.
5. (Previously Presented) Plasma source apparatus according to claim 1 comprising several axial conductive segments, each axial conductive segment interconnecting said conductive loop elements.

6. (Previously Presented) Plasma source apparatus according to claim 1 comprising antenna cooling means such as a chiller, a heat pipe, a Cryo-cooler or a Peltier device.

7. (Previously Presented) Plasma source apparatus according to claim 1 comprising thermal control means of the plasma generation chamber in order to avoid thermal shock between the inside and the outside of the plasma generation chamber during especially the plasma ignition.

8. (Previously Presented) Plasma source apparatus according to claim 1 comprising a matching network interconnecting the radio frequency generator and the antenna, in such a way as to promote the optimal transfer of radio frequency energy from the radio frequency generator to the antenna.

9. (Previously Presented) Plasma source apparatus according to claim 1 comprising a fixed or a moveable shield, enclosing but disconnected from the antenna which is adapted to define or to adjust in real time the optimal electromagnetic coupling between the antenna and the plasma.

10. (Previously Presented) Plasma source apparatus according to claim 1 wherein the axial conductive element(s) connect(s) directly to the shield through the capacitive element(s).

11. (Previously Presented) Plasma source apparatus according to claim 1 comprising a magnetic field generator arranged around the antenna.

12. (Previously Presented) Plasma source apparatus according to claim 1 wherein at least one of said capacitive element is tunable.

13. (Previously Presented) Plasma source apparatus according to claim 1 wherein said axial conductive element or at least one of said axial conductive segments is twisted.

14. (Previously Presented) Plasma source apparatus according to claim 1 wherein at least one of said conductive loop elements is movable.

15. (Currently Amended) Plasma source apparatus according to claim 1 coupled with an optical resonator comprising at least two mirrors (one partially reflecting) placed at the limits of the plasma generation chamber, and wherein ~~The~~ the mirrors are aligned to provide multiple reflections of lightwaves.

16. (Currently Amended) Plasma source apparatus according to claim 1 coupled with an apparatus generating cavitation bubbles by ultrasonic waves; the RF energy is then induces into the interior of the acoustic cavitation bubbles which act as nuclei for the ignition and the maintenance of the plasma, and wherein ~~The~~ the plasma generation chamber can contain the liquid from where the bubbles are generated.

17. (Previously Presented) Plasma source apparatus according to claim 1 coupled with a complementary plasma source as Electron cyclotron resonance source or Ion cyclotron resonance source.

18. (Previously Presented) Plasma source apparatus according to claim 1 coupled with a complementary antenna inside or outside the plasma generation chamber.

19. (Previously Presented) Plasma source apparatus according to claim 1 wherein the antenna is also adapted as a receiving system to perform Nuclear Magnetic Resonance (NMR) Monitoring or analysis of fluid or a workpiece implemented inside the plasma generation chamber.

20. (Previously Presented) Plasma source apparatus according to claim 1 wherein each of said axial conductive segment(s) and/or said conductive loop elements are made with volume conductive wire, or braids wire, typically Litz wire, or hollow wire.

21. (Previously Presented) Plasma source apparatus according to claim 1 comprising a network of antennas as defined in the previous claims wherein adjacent pairs of conductive loop elements have at least one common axial conductive segment.

22. (Previously Presented) A plasma source apparatus according to claim 1, being connected to one or a plurality of process chamber.

23. (Previously Presented) A plurality of plasma source apparatuses according to claim 1, each plasma sources being cooperatively connected to at least one process chamber.

24. (Currently Amended) One or a plurality of plasma source apparatuses according to ~~the~~ claim 1 comprising a plurality of RF coils, the RF coils being arranged in a circumferential manner proximate to the process chamber(s).

25. (Previously Presented) One or a plurality of plasma source apparatuses according to claim 1 wherein at least one RF coils comprises a capacitive element.

26. (Previously Presented) One or a plurality of plasma source apparatuses according to claim 22 comprising a plurality of magnets, the magnets being arranged in a circumferential manner proximate to the process chamber(s), for exemple, to perform NMR inspection the process chamber and/or the workpiece(s) inside.

27. (Previously Presented) One or a plurality of plasma source apparatuses according to claim 22 comprising a plurality of electrodes defining a Paul trap type or a Penning trap type on which an oscillating voltage is applied.

28. (Cancelled).

29. (Cancelled).